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Int'l Filing Date : November 17, 2003

AMENDMENTS TO THE CLAIMS

Please amend the Claims as follows. Insertions are shown underlined while deletions are ~~struck through~~. Please add Claims 11-

1 (original): A curing resin composition containing a siloxane oligomer (A) having an average molecular weight of 500 to 10000 in terms of ethylene glycol and a fluorine compound (B) having a fluoroalkyl structure and a polysiloxane structure and having a number average molecular weight of 5000 or more in terms of polystyrene.

2 (original): The curing resin composition according to claim 1, wherein a fluorine atom content in the curing resin composition is 20 wt % or more.

3 (currently amended): The curing resin composition according to claim 1-~~or 2~~, further containing a crosslinking compound.

4 (currently amended): The curing resin composition according to ~~any of~~ claims 1-~~to~~ 3, further containing an acid generating agent.

5 (currently amended): A cured film obtained by curing a curing resin composition according to ~~any of~~ claims 1-~~to~~ 4.

6 (original): The cured film according to claim 5, wherein a ratio (Si/F) of a peak intensity of a silicon atom (Si) to a peak intensity of a fluorine atom (F) on a surface of the cured film as measured with an X-ray photoelectron spectroscopic method is in the range of from 0.4 to 2.

7 (currently amended): An antireflection film comprising a hard coat layer formed on one surface of a transparent substrate directly or with another layer interposed there between and an antireflection layer laminated on a surface of the hard coat layer, wherein the antireflection layer is constituted of a cured film according to claim 5-~~or 6~~.

8 (original): The antireflection film according to claim 7, wherein a surface of the hard coat layer has irregularity of protrusions and depressions combined and an antiglareness.

9 (currently amended): An optical element on one surface or both surfaces of which an antireflection film or antireflection films according to claim 7-~~or 8~~ are provided.

10 (currently amended): An image display to which an antireflection film according to claim 7-~~or 8~~ or the optical element according to claim 9 is mounted.

11 (new): The curing resin composition according to claim 2, further containing a crosslinking compound.

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12 (new): The curing resin composition according to claim 2, further containing an acid generating agent.

13 (new): The curing resin composition according to claim 3, further containing an acid generating agent.

14 (new): The curing resin composition according to claim 11, further containing an acid generating agent.

15 (new): A curable resin composition comprising:

(A) a siloxane oligomer having an average molecular weight of 500 to 10000 in terms of ethylene glycol; and

(B) a fluorine compound having a fluoroalkyl structure and a polysiloxane structure and having a number average molecular weight of 5000 or more in terms of polystyrene, wherein a ratio of A/(A+B) by solid weight is 0.05-0.9,

said composition being curable by heat or active light irradiation by reacting the siloxane oligomer and the polysiloxane structure in the fluorine compound.

16 (new): The curable resin composition according to claim 15, wherein the fluorine compound contains a hydroxyl group and/or an epoxy group which are reactive with the siloxane oligomer or the polysiloxane structure in the fluorine compound.

17 (new): The curable resin composition according to claim 15, further comprising a crosslinking agent in an amount of 70 parts or less by weight with respect to the fluorine compound.

18 (new): A cured film using the curable resin composition of claim 15, having a cured structure of: (A) the siloxane oligomer glycol and (B) the fluorine compound, said siloxane oligomer and said polysiloxane structure in the fluorine compound being reacted.

19 (new): The cured film according to claim 18, which has an additional cured structure wherein the fluorine compound contains a hydroxyl group and/or an epoxy group which have reacted the siloxane oligomer or the polysiloxane structure in the fluorine compound.